

Docket No. 372106-102
US App. No. 10/616,731

REMARKS

Claims 1-33 are currently pending in this application. Claims 1-16 and 21-29 have been withdrawn from consideration. Claims 30-33 have been added. Claims 17 and 18 have been amended. No new matter has been added. Support for the amended claims can be found in the original claims 1 and 17, and in the specification on page 24, lines 21-23 and on page 28, lines 14-18. Support for the added claims can be found in original claims 2 and 17, and in the specification on page 24, lines 21-23; in original claim 18, and in the specification on page 28, lines 14-18; and in original claims 19 and 20.

The following remarks put the pending claims in condition for allowance. Applicants respectfully request reconsideration and the timely allowance of the pending claims.

35 USC § 102(e) Rejection by Yamada et al. or Kurosawa et al.

Claims 17 stands rejected under 35 U.S.C. §102(e) as being anticipated by Yamada et al., U.S. Patent No. 6,737,118, (hereinafter "Yamada") or in the alternative by Kurosawa et al., U.S. Patent No. 6,410,151, (hereinafter "Kurosawa").

Yamada, at the top of column 13 of the specification, teaches that the coated film is first dried and subsequently subjected to a heat treatment at a temperature of 350°C to 650° C in a furnace that has an oxygen concentration of no greater than 100 ppm. Yamada states that if the heat treatment temperature is above 650 °C, all of the organic groups will decompose, so that the moisture adsorption will increase considerably and the relative dielectric constant will be raised by hydroxyl groups in the film. The Examples of Yamada only show heat treatments at 450 °C. In contrast, the present invention, as claimed, recites a heat treatment temperature of between 680°C to 750°C. By carrying out the heat treatment at such a high temperature, the denseness of the film increases and the resistance to hydrofluoric acid of the resulting silica-based organic film is improved and, furthermore, degassing due to atmospheric temperature increase is suppressed, as explained in the specification on page 25, lines 1-5. As such, the silica-based organic

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film of the present invention has superior properties compared to the film of Yamada. Accordingly, Yamada fails to teach each and every limitation of the claims. Therefore, Applicants respectfully request the withdrawal of the rejection based on this reference.

Kurosawa discloses a heat treatment of silica based film at temperature of 450°C or lower (see column 16, lines 50-53 of the specification). This heat treatment temperature is far lower than the claimed heat treatment temperature of the present invention. As discussed above, the high heat treatment temperature of the present invention provides a silica-based organic film with superior properties compared to a film formed from lower heat treatment temperatures. Thus, Kurosawa also fails to anticipate the present invention. As such, Applicants respectfully request the withdrawal of the rejection based on this reference.

35 USC § 103(a) Rejection over Yamada et al. or Kurosawa et al.

Claim 10 stands rejected under 35 U.S.C. § 102(e) as being anticipated by Yamada or Kurosawa or, in the alternative under 35 U.S.C. § 103(a) for allegedly being unpatentable over Yamada or Kurosawa.

Claims 18-20 have been amended to depend from claim 17. As discussed above, neither Yamada nor Kurosawa teaches or suggests all the limitations of claim 17. Thus, claims 18-20 are patentable over the prior art for at least these reasons. Accordingly, Applicants respectfully request the withdrawal of the rejections under 102 or 103 of these claims.

Newly Added Claims

Claims 30-33 have been added. These claims contain all the limitations of claim 17. Accordingly, these claims are allowable over the prior art for at least the reasons forwarded for the patentability of claim 17.

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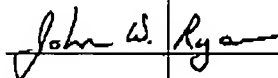
CONCLUSION

Applicants believe this response to be a full and complete response to the Office Action. In view of the foregoing, Applicants respectfully request reconsideration and allowance of claims 17-20 and 30-33. As the application is believed to be in condition for allowance, Applicants respectfully request a Notice of Allowability. The Examiner is invited to contact the undersigned representative should any further issues arise

Respectfully submitted,

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